

## Information Disclosure Citation Listing

<b>Form PTO-1449</b> U.S. Department of Commerce (Rev. 7-80) Patent and Trademark Office 42-44F (F-49) <b>INFORMATION DISCLOSURE CITATION</b> (Use several sheets if necessary)		<b>Atty. Docket No.:</b> F-9089		<b>Serial No.:</b> 10/578,047			
		<b>Applicant:</b> Joachim MAI, et al.					
		<b>Filing Date:</b>		<b>Group:</b>			
<b>U.S. PATENT DOCUMENTS</b>							
<b>Examiner Initial</b>		<b>Document Number</b>	<b>Date</b>	<b>Name</b>	<b>Class</b>	<b>Subclass</b>	<b>Filing Date If Appropriate</b>
		US-					
<b>FOREIGN PATENT DOCUMENTS</b>							
		<b>Document Number</b>	<b>Date</b>	<b>Country</b>	<b>Class</b>	<b>Subclass</b>	<b>Translation</b>
							<b>Yes</b> <b>No</b>
	F1	DE- 4108404	10/10/1991	DE			N*
	F2	DE- 39724	1/23/1964	DE			N <sup>P</sup>
TRANSLATION KEY: * English Abstract. <sup>F</sup> Concise statement of relevance provided in foreign search report. <sup>C</sup> Concise statement of relevance provided in specification or in attachment to document. <sup>S</sup> Concise statement of relevance provided in IDS. <sup>P</sup> Relevant portion of document translated. <sup>O</sup> English abstract only - copy of document in pct search.							
<b>OTHER INFORMATION DISCLOSURE CITATIONS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>							
	01	5/21/2003 "Reactive etching of semiconductor surfaces using an electronically chopped low energy broad beam ion source" J. Dienelt et al. Elsevier Science B.V., Surface and Coatings Technology Volumes 174-175 Pages 157-161					
	02	7/17/2003 "Generation of a pulsed ion beam with a tuned electronic beam switch" J. Dienelt et al. Plasma Sources Science and Technology Vol. 12 Pages 489-494					
<b>EXAMINER</b>				<b>DATE CONSIDERED</b>			
<b>EXAMINER:</b> Initial if reference considered, whether or not citation is in conformance with MPEP 609; Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.							